Annealsys RTP Machines Brief Description

AS-Micro

Applications .... : RTA, RTO, Reflow, Implantation annealing…

Substrate size .... : up to 3-inch diameter

Temperature max................ : 1250°C

Temperature ramp rate .... : 250°C/s on 2-inch silicon wafer

Temperature control .... : thermocouple (pyrometer option), fast PID

Vacuum capability .... : 10^{-3} Torr (10^{-6} Torr option)

Gas lines............................. : up to 4 gas lines with MFC and one purge line with needle valve

Loading .... : manual, optional interface for glove-box

Number of process tubes...... : 1 or 2

Product link (1): http://www.annealsys.com/annealsys-products/rtp-rtcvd/as-micro.html

AS-One 100 & AS-One 150

Applications .... : RTA, RTO, Reflow, Implantation annealing…

Substrate size .... : up to 4-inch, 6-inch diameter samples depending on model

Temperature max................ : 1450°C (depending on furnace version)

Temperature ramp rate .... : 200°C/s on 4-inch silicon wafer, (depending on version)
150°C/s on 6-inch silicon wafer, (depending on version)

Temperature control .... : thermocouple or pyrometer, fast PID

Vacuum capability .... : 10^{-3} Torr (10^{-6} Torr option)

Gas lines............................. : up to 5 gas lines with MFC and one purge line with needle valve

Loading .... : manual

Product link: http://www.annealsys.com/annealsys-products/rtp-rtcvd/as-one.html

AS-Premium

Applications .... : RTA, RTO, Reflow, Implantation annealing…

Substrate size .... : up to 200x200 mm^2 samples

Temperature max................ : 1300°C (depending on furnace version)

Temperature ramp rate .... : 150°C/s on 4-inch silicon wafer (depending on version)

Temperature control .... : thermocouple or pyrometer, fast PID

Vacuum capability .... : 10^{-3} Torr (10^{-6} Torr option)

Gas lines............................. : up to 6 gas lines with MFC and one purge line with needle valve

Loading .... : manual, optional cassette to cassette

Product link: http://www.annealsys.com/annealsys-products/rtp-rtcvd/as-premium.html

Zenith

Applications .... : Silicon Carbide implantation annealing, Graphene on SiC…

Substrate size .... : up to 4-inch diameter samples

Temperature max................ : 2000°C

Temperature ramp rate .... : 1°C/s on 4-inch graphite susceptor

Temperature control .... : thermocouple and pyrometer, fast PID

Vacuum capability .... : 10^{-6} Torr

Gas lines............................. : up to 8 gas lines with MFC and one purge line with needle valve

Loading .... : manual

Product link: http://www.annealsys.com/annealsys-products/high-temp-rtp/zenith-100.html

AS-Master

Applications .... : RTA, RTO, RTCVD, Reflow, Implantation annealing…
Substrate size .... : up to 8-inch diameter
Temperature max. .... : 1450°C (depending on version)
Temperature ramp rate .... : 200°C/s on 8-inch silicon wafer (depending on version)
Temperature control .... : multi-zone, thermocouple or pyrometer, fast PID
Vacuum capability .... : 10^{-3} Torr (10^{-6} Torr option)
Gas lines.............................. : up to 6 gas lines with MFC and one purge line with needle valve
Loading .... : manual, optional cassette to cassette
Product link: http://www.annealsys.com/annealsys-products/rtp-rtcvd/as-master.html

(1) "Product links" always point to the product and are not subject to change even if there is some modification in the description of the product. This link can be used reliably over time